

## APPENDIX

5. (amended) A method according to ~~any one of Claims 1 to 4~~claim 1, wherein the covering layer extends from both ends of the line in similar manner and the plating potential is applied at both ends of the line during the plating process.
6. (amended) A method according to ~~any one of Claims 1 to 5~~claim 1, wherein the covering layer comprises photoresist.
7. (amended) A method according to ~~any one of Claims 1 to 6~~claim 1, wherein the step of forming the lines comprises:
- depositing a layer of transparent conducting material (53) over the substrate (46),
  - depositing a photoresist layer (54) over the layer of transparent conducting material and patterning the photoresist into a configuration corresponding to the desired lines,
  - patterning the transparent conducting layer using the photoresist to leave the lines of transparent conducting material.
9. (amended) A method according to ~~Claim 7 or Claim 8~~claim 7, and for use in the manufacture of a pixellated device comprising pixel electrodes (38) of transparent conducting material carried together

with the conductive lines, on the substrate (46), wherein the photoresist layer (54) is patterned into a configuration corresponding also to the desired pixel electrodes, and wherein the transparent conducting layer (53) is patterned using the photoresist to leave pixel electrode regions (57).

13. (amended) A method according to ~~Claim 11 or Claim 12~~claim 11, wherein the photoresist is defined to leave on each line a similar photoresist region extending from the other end part and wherein the plating potential is applied also at that other end part.

14. (amended) An active matrix liquid crystal display device comprising an active plate (82) made according to ~~any one of Claims 11 to 14~~claim 11, a further substrate (83) carrying an electrode structure spaced from the active plate, and liquid crystal (81) disposed between the active plate and the further substrate.